JAN 1,0 2005

PTO/SB/08a (08-03)
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet 1 of 3

Substitute for form 1449A/PTO

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Complete if Known				
Application Number	10/665,934			
Filing Date	09/19/2003			
First Named Inventor	Liu, et al.			
Art Unit	2812			
Examiner Name	Unassigned			
Attorney Docket Number	7989/ETCH/SILICON/JB1			

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Translation is attached.

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Substitute for form 1449B/PTO Complete if Known Application Number 10/665,934 SUPPLEMENTAL INFORMATION Filing Date 09/19/2003 DISCLOSURE STATEMENT BY First Named Inventor Liu et al. APPLICANT Art Unit 2812 (Use as many sheets as necessary) Examiner Name Unassigned 7989/ETCH/SILICON/JB1 of 3 Sheet Attomey Docket Number **U.S. PATENT DOCUMENTS** Pages, Columns, Lines, Where Document Number Publication Date Examiner Name of Patentee or Applicant of Cited Document Relevant Passages or Relevant Initials MM-DD-YYYY Figures Appear Number - Kind Code2 (if known) US-5,944,940 08/31/1999 TOSHIMA Ви US- 5,926,690 07/20/1999 TOPRAC, ET AL. RN US- 5,913,102 06/15/1999 YANG BU US-5.653.894 08/05/1997 IBBOTSEN, ET AL. ĸш US- 5,452,521 09/26/1995 NIEWMIERZYCKI BA US-5,171,393 12/15/1992 MOFFAT BIL US-5,109,430 04/28/1992 NISHIHARA, ET AL. RN US- 4,911,103 03/27/1990 DAVIS, ET AL. Ru US- 4,447,731 05/08/1984 KUNI, ET AL. BN **FOREIGN PATENT DOCUMENTS** Foreign Patent Document Pages, Columns, Lines, Where Examiner Cite No.1 **Publication** Name of Patentee or Applicant Relevant Initials* Date MM-DD-YYYY of Cited Document Passages or Country Code3 - Number4 - Kind Code5 (if known) Relevant Figures T⁶ Appear WO 01/09934 A1 02/08/2001 Williams, et al. WO 02/37186 A1 05/10/2002 Brill, et al. WO 03/003447 A2 01/09/2003 Rangarajan, et al. EP 1 083 424 03/14/2001 Hunter, et al. EP 1 079 428 02/28/2001 Adams, et al. WO 02/09170 A2 01/31/2002 Drake, et al. WO 01/84382 A1 11/08/2001 Lakkapragada, et al. EP 0 727 715 08/12/1996 AT&T Corp. JP 61 290312 BU 12/20/1986 Hitachi Ltd. NON PATENT LITERATURE DOCUMENTS Examin include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of Cite T² the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue Initials * No. number(s), publisher, city and/or country where published. YANG, ET AL., "Line-Profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002. KOTA, ET AL., "Advanced Process Control for Polysilicon Gate Etching Using Integrated Optical CD Metrology", Proceedings of SPIE, Vol. 5044 (2003) pp. 90-96.

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Date

Considered

2/12/2005

BU Examiner

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	Substitute for form 14498/PTO					Complete if Known		
	SUPPLEMENTAL INFORMATION					Application Number	10/665,934	
						Filing Date	09/19/2003	
	DISCLOSURE STATEMENT BY APPLICANT				II BY	First Named Inventor	Liu et al.	
						Art Unit	2812	
		(Use as ma	any sheets	as necessa	ry)	Examiner Name	Unassigned	
こ	Sheet	3	of	3		Attomey Docket Number	7989/ETCH/SILICON/JB1	

Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
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Examiner		Date	
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